M olecular dynam ics study of m elting of a bcc m etal-vanadium II: therm odynam ic m elting

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A bstract

We present molecular dynamics simulations of the thermodynamic melting transition of a box metal, vanadium using the Finnis-Sinclair potential. We studied the structural, transport and energetic properties of slabs made of 27 atomic layers with a free surface. We investigated premelting phenomena at the low-index surfaces of vanadium; V(111), V(001), and V(011), nding that as the temperature increases, the V(111) surface disorders rst, then the V(100) surface, while the V(110) surface remains stable up to the melting temperature. Also, as the temperature increases, the disorder spreads from the surface layer into the bulk, establishing a thin quasiliquid limin the surface region. We conclude that the hierarchy of premelting phenomena is inversely proportional to the surface atomic density, being most pronounced for the V(111) surface which has the lowest surface density.

1 Introduction

Theories of melting [1, 2, 4, 7] can be separated into two classes. The rst one describes the mechanical melting of a homogeneous solid resulting from lattice instability [3, 6, 8] and/or the spontaneous generation of thermal defects [9, 10, 12, 13]. The second class treats the thermodynamic melting of heterogeneous solids, which begins at extrinsic defects such as a free surface or an internal interface (grain boundaries, voids, etc.) [4, 5, 11, 15, 34, 16, 17, 26].

Both types ofm elting have been studied extensively for the case of from etals. In order to determ ine whether the mechanism of hom ogeneous melting diers if the lattice symmetry is changed, in our rst paper [14], we extended these studies to a boom etal, vanadium. We used molecular dynamics simulations to study the mechanical melting transition in a bulk system, and found that the melting transition occurs uniformly throughout the solid at the melting point. The shear elastic instability leading to this melting of vanadium occurred once the molar volume reached a critical value, whether reached by heating the solid or by adding defects at a constant temperature [14]. The temperature at which the mechanical melting transition takes place in our model is $T_{\rm s}=2500-10~{\rm K}$, which is above the melting temperature measured experimentally, $T_{\rm m}=2183~{\rm K}$. Thus, the mechanical melting transition can be observed only if melting at surfaces is articially suppressed, since in the laboratory it is preempted by the thermodynamic melting transition which begins at a free surface.

Theoretical aspects of melting beginning at the surface have been studied by phenom enological theories [16, 18, 19, 20, 21], lattice-gas models [17], and density functional theory [22]. Microscopic descriptions of static and dynamic properties of melting phenomena beginning at a surface emerged from computer simulations which employ many-body interaction potentials derived from the ective-medium [23, 24, 25] and embedded-atom theories [27, 28, 26, 31, 29], as well as pairwise interatomic interactions in the form of Lennard-Jones potentials [32, 33]. Melting at the surface is anisotropic, meaning that certain surfaces of from etals (Pb (110), A 1(110)) exhibit premelting, [16] while this phenomenon is not observed for the close-packed surfaces (Pb (111), A 1(111)). Theoretical aspects of this anisotropy were discussed by Trayanov and Tosatti [17].

This paper is organized as follows: details of the molecular-dynamics simulations are presented in Sec. II. Sec. III contains most of the results of this study, including the thermodynamic melting temperature and several structural, energetic, and transport properties of the surface. Finally, in Sec. IV, we sum marize our results.

2 Simulation details

We model the melting of vanadium with a free surface using molecular dynamics (MD) simulations [39, 40] in a canonical ensemble. The many-body

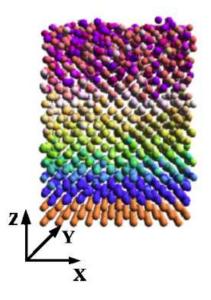


Figure 1: Geometry of the sample (V (001) surface).

interaction potential used in this study was developed by Finnis and Sinclair [38] (FS). The computational aspects of the algorithm are described in detail in our previous article [14].

Ideally, a crystal with a surface is a sem i-in nite system. We modeled this system as a thick slab. This slab is shown in Fig. 1. The bottom 3 atom ic layers have the positions of the atom s xed in order to mim ic the e ect of the presence of the in nite bulk of the crystal. Due to the relatively short range of the repulsive part of the modiled FS potential, 3 xed layers are suicient to represent the static substrate. On top of those 3 layers there are 24 layers in which the atom sare free to move. Periodic boundary conditions are used along the in-plane (x and y) directions, while the top boundary of the slab, along the z direction, is free. In Figure 1 we show a sample where the temperature is high enough so that the layers near the free surface are already disordered.

Three di erent sam ples with various low-index surfaces were constructed: V(001), V(011) and V(111), whose surface layers are shown in Fig. 2. The V(001) and V(111) sam ples contain 2700 atom s, initially arranged as a perfect box crystal of $10 \times 10 \times 27$ unit cells (100 atom s in a layer). The V(011) sam ple contains 2646 atom s arranged as $7 \times 7 \times 27$ unit cells (98 atom s in a

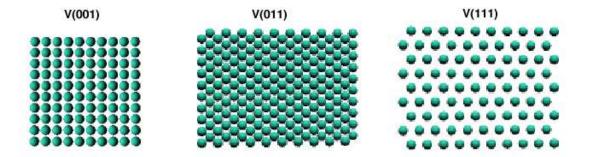


Figure 2: Geometry of the low-index faces of vanadium (top view). The drawings are to scale.

layer).

Each simulation starts from a low-temperature solid. The lattice constant of the frozen layers is assigned a value appropriate to the bulk [14]. As the tem perature is raised, this value is adjusted to re ect therm alexpansion as obtained from bulk simulations[14]. We found that 10⁵ integration time steps were su cient in order to reach thermal equilibrium after a temperature change (a time step dt = 1.0510 15 sec). An equilibrium state is considered to be achieved when there is no signi cant temporal variation (beyond the statistical uctuations) of the total energy, layer occupation num ber, structure order param eters, self di usion coe cients, and a uniform pro le of kinetic tem perature across the sam ple is observed. Thereafter the various structural and transport properties of the system are calculated, accum ulated and averaged over a long period of 107 MD steps. Throughout this study, interactive visualization (the AV iz program [41]) was in plemented, to observe sample disorder and layer mixing (see Fig.1). A discussion of this visualization can be found in Ref. [45].

3 Premelting e ects on surfaces

3.1 Therm odynam ic melting temperature

In order to investigate the phenom enon of surface disorder and premelting, we rst determ ined the therm odynam ic melting point $T_{\rm m}$ of vanadium described by the modi ed FS potential. $T_{\rm m}$ was obtained by means of the method

proposed by Lutsko et al. [42]. In this way, we found $T_m=2220-10 \, \mathrm{K}$ for the V (111) sample, which has the lowest surface packing density. This value is close to the experimental value [43] of $T_m=2183 \, \mathrm{K}$. For the other surfaces, the value of T_m comes out slightly higher, but within the uncertainty limits of the simulation. The dierence could be due to superheating elects on the solid-liquid interface just above the thermodynamical melting point T_m . The largest dierence is found for the close packed V (011) surface, with $T_m=2240-10 \, \mathrm{K}$. This dependence of the thermodynamic melting point on the crystalline plane forming the surface was also observed in MD simulations of fix metals [23, 25, 27, 28, 13].

3.2 Surface therm alexpansion and am plitude of atom ic vibration

The interlayer relaxation and surface them alexpansion was calculated using the dierence between the average z coordinate of the ith and i+ 1th layers:

$$d_{i;i+1} = \frac{1}{n_{i+1}} \sum_{j:2 \ i+1}^{X} z_j \frac{1}{n_i} \sum_{j:2 \ i}^{X} z_j$$
 (1)

where z_i is the z-coordinate of the atom i, n_i is the instantaneous number of atom s in the layer i, and the angular brackets denote a time average. The distances between the neighboring layers could be determined up to the temperatures where surface premelting elects blur the distinction between individual layers, although some structure remains visible in the local density proles (see below).

At low temperatures, the rst layer exhibits an inward relaxation, i.e. $_{1,2} < 0$, where we de ne

$$a_{i;i+1} = \frac{d_{i;i+1} d_{bulk}}{d_{bulk}}$$
 (2)

where $d_{i;i+1}$ is the distance in the z-direction between the i and i+ 1 surface layers, and d_{bulk} is the distance between two neighboring layers in the bulk. In Figures 3 and 4 $_{i;i+1}$ is plotted versus temperature for the two of the low-index faces.

The e ect of the di erent geom etry of the various surfaces is re ected in the thermal expansion, i.e. a surface with a lower atom ic density expands more than a surface which is close packed. As shown in Fig. 5, the thermal

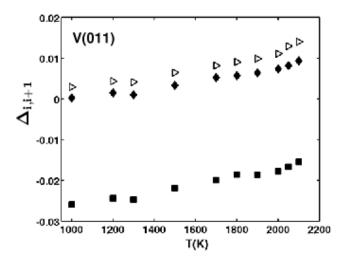


Figure 3: Plot of $_{i;i+1}$ for the rst (squares), second (triangles) and third (diam onds) surface layers as a function of tem perature for the V (011) surface.

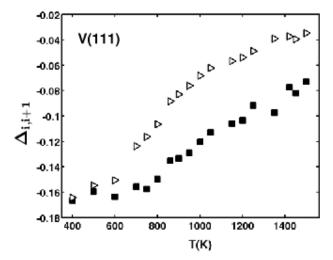


Figure 4: Plot of $_{i,i+1}$ for the rst (squares) and second (triangles) surface layers as a function of temperature for the V (111) surface.

expansion of the V (111) surface layers is signi cantly larger than the therm all expansion of other surfaces and xed layers (bulk). In Fig. 6 we plot therm all expansion of surface layers (for the V (001) and V (011) slabs) and xed layers on an enlarged scale. The observed \anomalous" therm all expansion of these surface layers is a direct consequence of enhanced vibration at the surface, where atom sprobe them ore anharm onic region of the interatom ic potential. A nom alous therm all expansion was set observed in experiments on Pb (110) by Frenken [15].

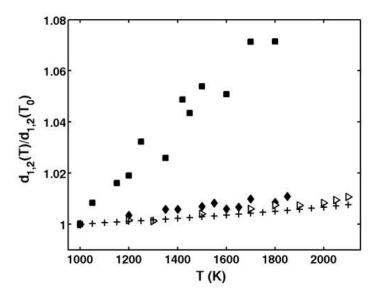


Figure 5: Normalized interlayer distances between the rst and second layers, $d_{1,2}(T)=d_{1,2}(T_0)$ at $T_0=1000$ K for the V (111) (squares), V (001) (diamonds), V (011) (triangles) surfaces and the bulk (crosses). Note the anomalous thermal expansion of the V (111) surface.

A tom ic vibration properties at the di erent faces of vanadium are important for illustrating the onset of anharm onicity at high temperatures. We calculate the mean square vibration amplitude (MSVA), $< u^2 >$, around the equilibrium position in the rst surface layer as:

$$< u^{2} > = \frac{1}{n_{1}} X^{n_{1}} h \times r_{i; (t)} < r_{i; (t)} > 1_{2}$$
 (3)

where = x;y;z denotes the spatial direction of motion, n_1 is the instantaneous number of atoms in the structure layer, and the angular brackets

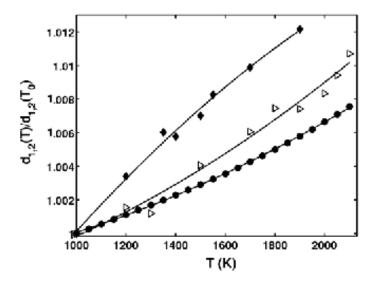


Figure 6: Normalized interlayer distances between the rst and second layers, $d_{1;2}(T) = d_{1;2}(T_0)$ at $T_0 = 1000$ K for the V (001) (diam onds) and V (011) (triangles) and the bulk (circles). The solid lines are drawn to guide the eye.

represent an average over time.

In a harm onic system , < u^2 > increases linearly with temperature, and therefore deviations from linearity are a measure of anharm onicity. The mean square amplitudes of vibration shown in Fig. 7 for the V (111) surface demonstrate substantial anharm onicity at elevated temperatures. Figure 7 also shows that there is a noticeable di erence between the in-plane M SVA , < u_x^2 > , and out-of-plane one, < u_z^2 > (we found that < u_x^2 > ' < u_y^2 >).

In-plane M SVA's are larger than out-of-plane am plitudes also for V (001) and V (011) surfaces. One reason for this anisotropy could be the dierent nearest neighbour distance along the x and z directions caused by the inward relaxation of the surface layer, leading to a net restoring force that is higher in the direction perpendicular to the surface. The in-plane components of the mean square amplitudes of vibration for the various faces of vanadium are shown in Fig. 8. As may be seen from the gure the in-plane M SVA is largest for the V (111), and smallest for the V (011) surface. A tom swhich belong to the loose-packed surface V (111) are less tightly bound than atom s of the close-packed V (011) face, and therefore vibrate with larger amplitudes.

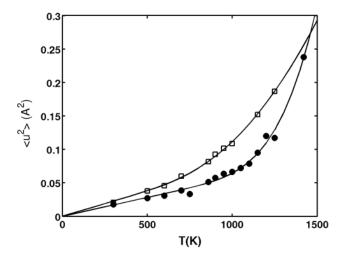


Figure 7: M ean-square am plitudes of vibration < u_z^2 > (led circles) and < u_x^2 > (squares) for the rst layer of the V (111) surface as a function of tem perature. The solid lines are a t to the data.

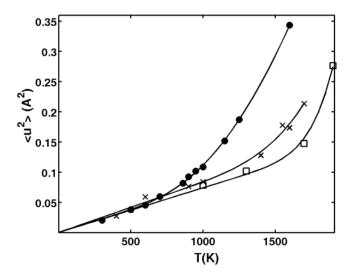


Figure 8: The calculated in-plane compoments of mean square amplitudes of vibration $< u_y^2 >$ for the rst surface layer of V (111) (led circles), V (001) (croses) and V (011) (squares) as a function of temperature. The solid lines are a to the data.

3.3 Layer density pro les

In order to display the structure of the sample along the z direction, perpendicular to the surface, it is convenient to use the density (z), de ned so that (z)dz is the number of atom s in a slice of thickness dz at z. We represent (z) by a continuous function de ned according to Chen et al. [27, 28]

$$(z) = \frac{1}{2} \sum_{i=1}^{X} \exp\left(-\frac{(z - z_i)^2}{2 z}\right)^{+}$$
 (4)

where z_i is the z coordinate of atom i, with z=0 set at the bottom of the rst layer which is not xed_p and the angular brackets indicate a time average. We use $z=0.1a_0=2$ 3, where a_0 is the bulk lattice parameter at a given temperature. For a system in equilibrium, (z) can be obtained by an average over many dierent con gurations. Plots of (z) at dierent temperatures are given in Fig. 9 for the V (111) slab, in Fig. 11 for the V (011) slab and in Fig. 10 for the V (001) slab.

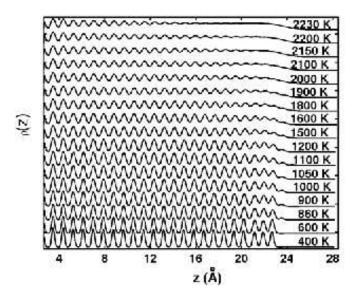


Figure 9: Density pro le across the V (111) slab along the z direction at various tem peratures.

Premelting e ects at the crystal surface can be examined by monitoring the layer-by-layer modulation of the density pro le of the system, (z), at

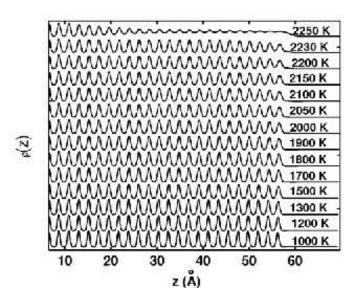


Figure 10: Density pro le across the V (011) slab along the z direction at various tem peratures.

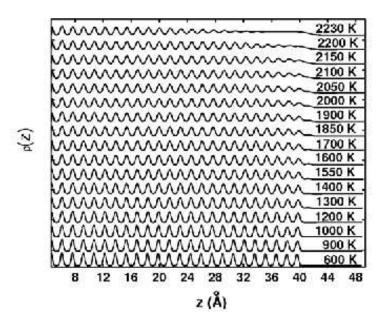


Figure 11: Density pro le across the V (001) slab along the z direction at various tem peratures.

various tem peratures up to the melting point T_m . At low tem peratures (z) consists of a series of well resolved peaks. The atoms are packed in the layers with constant density in each layer and virtually no atoms in between these layers. As the tem perature increases the elective width of each layer becomes broader due to the enhanced atomic vibration. The position of the density peaks moves to larger values of z due to the thermal expansion. At higher tem peratures the atomic vibration becomes so large, especially in the topmost layers, that the minima of (z) in between two layers rise to non-zero values. In addition, disorder sets in, with atomic migration taking place between the layers. Comparing Figs. 9-11, one can see that the V (111) surface crosses over to a state of premelting rst, than V (001), while on the V (011) surface premelting elects are very small.

Above som e tem perature (T_{pm} ' 1000 K for the V (111) surface, T_{pm} ' 1800 K for the V (001) surface, T_{pm} ' 2200 K for the V (011) surface) the density of the topm ost layer becomes slightly lower than that of the underlying layers. This loss of density is compensated by the appearance of an adlayer. The ad layer appears rst on the least packed surface V (111), and then at a higher tem perature on the V (001) surface. The close packed face V (011) develops an adlayer at tem peratures very close to $T_{\rm m}$. This hierarchy indicates that the form ation energy of structural defects (vacancy-adatom pairs) is dierent on these surfaces. That hierarchy was also observed in the investigation of the surface premelting of fcc metals (A 131, 30], Ni [27, 28, 29, 25], and Cu [27, 26]), where it was found that an adlayer appears rst on the least packed (011) surface, then at higher tem perature on the (001) face, and nally on the close packed (111) surface at a tem perature close to T_m . As the tem perature increases towards T_m the distinction between the surface layers becom es blurred, which is consistent with the topm ost layers converting into a quasiliquid.

3.4 Layer structure factors

The preceding section dealt with the onset of disorder along the z direction, perpendicular to the surface. In order to monitor the onset of in-plane disorder in each atom ic layer, it is useful to de ne a structure factor (order param eter), 1; , through a Fourier transform of the atom ic density which is

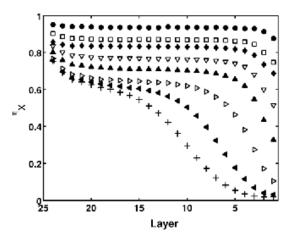


Figure 12: In plane structure factor, $_{\rm x}$, of the V (111) slab along the x direction vs layer number at several temperatures: T = 400K (circles), T = 860K (squares), T = 1100K (diamonds), T = 1500K (triangles down), T = 1800K (triangles up), T = 2100K (triangles left), T = 2200K (triangles right), and T = 2230K (crosses).

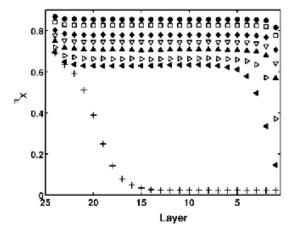


Figure 13: In-plane structure factor, $_{\rm x}$, of the V (011) slab calculated along x direction vs layer number at several temperatures: T = 1000K (circles), T = 1200K (squares), T = 1500K (diamonds), T = 1700K (triangles down), T = 1900K (triangles up), T = 2100K (triangles left), T = 2230K (triangles right), and T = 2250K (crosses).

calculated separately for each layer

$$\frac{1}{n_1^2} = \frac{1}{n_1^2} \sum_{j \ge 1}^{X} \exp(ig x_j)$$
 (5)

where = x; y and g = 2 = a e is a set of reciprocal lattice vectors. a is the distance between nearest neighbors, and n_1 is the instantaneous number of atoms in the layer 1. The sum extends over the particles in the layer 1, and the angular brackets denote averaging over time.

For an ordered crystalline surface the structure factor is a unity at zero tem perature. Enhanced vibration and form ation of point defects lead to a decrease of the structure factor with increasing tem perature. This is illustrated in Figs. 12 and 13 where the structure factor along the x direction is plotted vs. layer number for the V (111) and the V (011) slab, respectively. It is seen that these e ects are most pronounced in the surface region. Vacancies do not directly a ect the order parameter, since a normalization procedure is employed during each measurement by using the instantaneous layer occupation, n_1 , of a layer. Nevertheless, vacancies have an indirect e ect on the order parameter by introducing a localized lattice distortion.

As Figs. 12 and 13 show, for the V (111) slab we found a continuous decrease of the in-plane order parameter. In contrast, the close packed V (011) sample exhibits a relatively abrupt decrease of the structure factor within less than 20K of the melting temperature.

3.5 Radial distribution function

The formation of a quasiliquid Im can be analyzed by using a plane radial distribution function de ned as

$$p_{1}(\mathbf{r}_{jj}) = \frac{1}{n_{1}} \frac{X}{\sum_{i:j\geq 1}^{X} \frac{(\mathbf{r}_{ij}, \mathbf{j}j} - \mathbf{r}_{jj})}{2 \mathbf{r}_{jj}}^{+}$$
 (6)

where $r_{ij,jj}$ is the component of the r_i r_j parallel to the surface plane, n_1 is the instantaneous number of atoms in layer 1, the sum extends over all particles in layer 1, and the angular brackets denote averaging over time.

The two-dimensional radial distribution function, $p(r_{jj})$, for several layers of the V (111) and V (011) slabs very close to T_m is shown in Figs. 14 and 15. As seen from the gures the intra-layer structure in these layers

changes gradually from crystalline to liquid-like as one approaches the surface. Particularly noticeable is the disappearance of the crystalline features in $p(r_{jj})$ that correspond to the second, third and other nearest neighbors. In addition to the heights of the peaks, the area under the $p(r_{jj})$ curve changes, which rejects the change in the density across the solid-liquid interface.

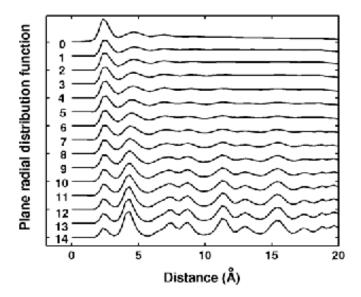


Figure 14: Two-dim ensional radial distribution function $p(r_{jj})$ of the top surface layers of V (111) at tem perature T=2230 K. The layer n=0 corresponds to the adlayer, n=1 to the rst layer, n=2 to the second one, etc.

We note that within the adlayer, the probability of nding particles with separation beyond the rst-neighbor shell is relatively small, indicating a tendency for clustering which persists, though to a smaller extent, even to T ' T_m . The plane pair-correlation functions for the rst layer of the V (001) at elevated tem peratures are shown in Fig. 16. It is clear that the crystalline structure vanishes gradually and the layer becomes quasiliquid as them elting point T_m is approached.

We conclude from the analysis of the plane radial distribution functions and density pro less that surface premelting begins rst on the least packed surface V (111), while changes only appear on the closed packed V (011) surface at temperatures which are very close to the melting point.

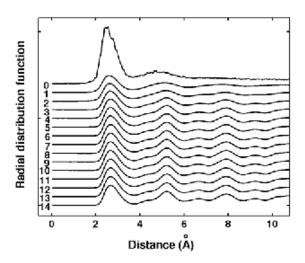


Figure 15: Two-dim ensional radial distribution function p (r_{jj}) of the surface layers of V (011) at tem perature T = 2230K . The layer n= 0 corresponds to the adlayer, n= 1 to the rst layer, n= 2 to the second one, etc.

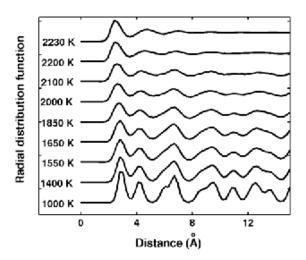


Figure 16: Two-dim ensional radial distribution function $p(r_{jj})$ of the $\ rst$ layer of V (001) at various tem peratures.

3.6 Layer occupation and point defects

As seen in the density pro les (Figs. 9-refdens001), the form ation of an adlayer on the least packed surface V (111) begins at around T $\,$ 800 K . At these temperatures, the appearance of an adlayer involves generation of vacancies only in the $\,$ rst surface layer, while at higher temperatures (T $\,$ 1600K) vacancies in the underlying layers (the second and third layers) begin to appear via promotion of atoms to vacant sites in the $\,$ rst surface layer. Atoms ignation from the deeper layers into the surface layers increases signicantly as the temperature approaches $\,$ T $_{\rm m}$. In contrast to the V (111) sample, adlayer form ation and generation of adatom-vacancy pairs at the the V (001) surface becomes observable only above T $\,$ 1400K (in practice, all adatoms come from the $\,$ rst layer).

The same eect, namely the appearance of an adlayer at dierent surfaces at successively higher temperatures was observed in computer simulations of surface premelting of ficemetals [23, 27, 28, 26, 31], where the lowest density (110) surface of ficemetals begins to disorder rst, while the close packed (111) surface preserves its ordered crystalline structure almost up to $T_{\rm m}$.

K now ledge of the equilibrium averaged number of atoms in the adlayer allows us to estimate E_s , the formation energy of a surface defect (adatom-vacancy pair) according to the relation:

$$n=N (T = 0) = \exp(E_s=k_B T)$$
 (7)

where n is the adlayer occupation number at a tem perature T , and N (T = 0) is the number of atoms in a layer at zero tem perature. Eq. (7) holds as long as the surface structure is preserved, and interactions between defects can be neglected. Hence, we used the adlayer occupation data in a tem perature region in which the concentration of adatom-vacancy pairs is small. The natural logarithm of adlayer occupation vs. $1=k_{\rm b}T$ is shown in Fig. 17 for the V (111), V (001) and V (011) surfaces, respectively. The calculated surface defect form ation energies of the various low-index faces of vanadium are tabulated in Table 1.

An alternative method of estimating values of E $_{\rm S}$ is to use the contribution of defects to anharm onicity, as rejected in the temperature dependence of the mean square vibration amplitude < u^2 > . Because the lattice in the vicinity of a defect is distorted, the value of < u^2 > will be larger for atoms near a defect. The layer averaged contribution to < u^2 > will therefore be proportional to the number of defects n, and hence to exp(E $_{\rm S}$ =k $_{\rm B}$ T). To

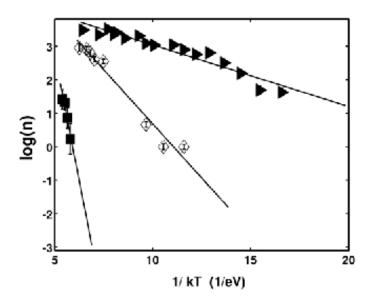


Figure 17: The natural logarithm of the equilibrium adatom concentration, n, as a function of $1=k_bT$ on the V (001), V (011) and V (111) faces (denoted by diam onds, triangles and squares, respectively.) The dashed lines are linear ts to the data.

extract E_s , we have the our $< u^2 >$ data to the form

$$< u^2 > = aT + b(T) \exp(E_s = k_B T)$$
 (8)

where a is a constant, and b(T) is a low order polynomial in T. We found that taking b(T) to be rst order in T, namely b(T) = bT, was su cient to obtain a good t. Typical ts were shown as solid lines in Figs. 7 and 8. Values of E $_{\rm S}$ deduced from these ts for the various surfaces are given in Table 1. There is good agreement between the values of E $_{\rm S}$ obtained by the two methods.

To sum marize this subsection, the formation energy of surface defects is lowest at the V (111) surface, and increases at the V (001) and V (011) surfaces. This hierarchy is consistent with the results obtained for various faces of copper (fcc lattice) by Hakkinen et al.[23] In both cases, the surface defect formation energy is largest for the close packed surfaces (V (011) in case of a bcc lattice, and Cu (111) in case of a fcc lattice), and lowest for the least packed surfaces, V (111) and Cu (011), respectively.

Table 1: Form ation energy, E_s , of adatom -vacancy pairs. Top line-Eq.(7), second line-Eq.(8). The data for Cu is from Ref. [23] Units are in eV.

Surface	(111)		(001)		(011)	
Va (bcc)	0 : 6	0:2 eV	0 : 67	0:03 eV	2 : 68	02 eV
Va (bcc)	0:53	0:05 eV	0 : 73	0:05 eV	2:5	0:3 eV
Cu (fcc) E _s	1 : 92 eV		0 : 86 eV		0:39 eV	

3.7 Di usion coe cients

M ass transport at surfaces can be characterized using the self di usion coe cients. These coe cients are found from the particle trajectories, r_{i} ; (t), by calculating the average m ean square displacem ent R $_{i}^{2}$.

$$R_{1;}^{2} = \frac{1}{n_{1}} \sum_{i \geq 1}^{X} \left[\mathbf{r}_{i;} (t+) \quad \mathbf{r}_{i;} () \right]^{2}$$
 (9)

where = x; y; z is a coordinate index, the sum includes atom s in the layer l, and the angular brackets denote averaging over time from the origin ().

The di usion coe cients D $_{\rm l}$; are calculated separately for each layer in the x;y and z directions, according to the E instein relation

$$D_{1;} = \lim_{t = 1}^{\infty} \frac{R_{1;}^{2}}{2t}$$
 (10)

Values of the di usion coe cients versus layer number are shown in Fig. 18. As expected, the mobility of atoms is larger the closer one comes to the surface. At high enough temperatures, where the surface layers become quasiliquid, the di usion coe cient is the same (within the error bars) for all the atoms in the region of the surface. These observations correlate with the structural variations in the surface region exhibited in the pair correlation functions, the structure order parameters, and local density proles.

The natural logarithm of the in-plane di usion coe cients, D $_{jj} = \frac{1}{2}$ (D $_{x}$ + D $_{y}$), for the first surface layer of the various faces vs. tem perature is shown in Fig. 19. Within our accuracy, the diffusion can be characterized by a simple exponential dependence throughout the whole tem perature range, D (T) / exp (E $_{d}$ =k $_{B}$ T), with diffusion activation energy, E $_{d}$, being independent of tem perature. Values of E $_{d}$ for the various low-index faces are given in Table 2. The diffusion coe cient of the least packed V (111) face is the largest. The

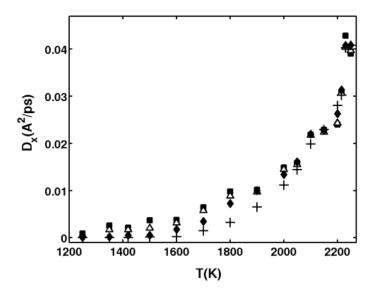


Figure 18: Di usion coe cients in layers, vs temperature, for the V (111) system along the x-direction ([110]). Squares correspond to the adlayer, l=0, triangles to the rst layer, l=1, diamonds to the second layer, l=2 and crosses denote coe cients of di usion in layer l=3.

di usion coe cient of V (001) is smaller, but still larger than the di usion coe cient of the close packed V (011) surface. In the tem perature range where the surface region is still solid-like, di usion takes place mainly by atoms exchanging places with vacancies. Writing $E_{\rm d}$ as a sum of the formation energy, $E_{\rm s}$, and migration energy, $E_{\rm m}$, and using the values of $E_{\rm s}$ from the preceding section, we can obtain values of $E_{\rm m}$ for the various surfaces. These are listed in Table 2. It is seen that the migration energy for the V (111) surface is again the lowest, while for the other two surfaces $E_{\rm m}$ is the same within the error bars of our calculation.

4 Conclusions

We investigated premelting elects at the various surfaces of vanadium using molecular dynamics simulations. We determined the thermodynamic melting temperature of vanadium described by the FS potential as 2220 10 K (V (111) surface), and studied structural, transport (diusion) and energetic

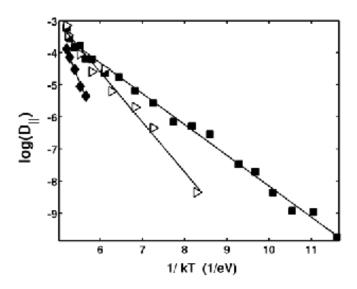


Figure 19: Plot of natural logarithm of the in-plane di usion coe cient $\log (D_{jj})$, for the various faces of vanadium as a function of inverse temperature. (D_{jj}) is in units of A^2 =psec.

Table 2: Calculated di usion activation energy E $_{\rm d}$ and m igration energy E $_{\rm m}$

<u> m</u>						
Surface	V (111)		V (001)		V (011)	
E _d (eV)	0:96	0 : 02 eV	1:56	0:03 eV	329	02 eV
E _m (eV)	0:43	0:07 eV	0 : 87	0:08 eV	0 : 79	0:5 eV

properties (form ation energy of surface defects).

We found that the surface region of V (111) begins to disorder rst, via the generation of vacancy-adatom pairs and a formation of an adlayer at temperatures above 1000 K . At higher temperatures, the surface region becomes quasiliquid. This process begins above 1600 K for the V (001) surface. At the closest packed V (011) surface, this elect is observed only in close proximity of $T_{\rm m}$.

The results of our simulations of surface premelting of the bcc metal, vanadium, are similar to the results obtained for various fcc metals, in the sense that the onset of disorder is seen as the surface with the lowest density.

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R eferences

- [1] A.R. Ubbeldone, Melting and Crystal Structure, Clarendon press, (Oxford) 1965
- [2] F. Lindem ann, Z. Phys, 11, 609, (1910).
- [3] M.Bom, Jour. Chem. Phys. 7, 591, (1939).
- [4] J.G.Dash, Rev. of Mod. Phys., 71, 71, (1999).
- [5] J.G. Dash, Contemprorary Physics, 43, 427, (2002).
- [6] J.L.Tallon, Phil. Mag. A 39, 151, (1979).
- [7] Y. Ida, Phys. Rev., 187, 951, (1969)
- [8] D.Wolf, P.R.Okamoto, S.Yip, J.F.Lutsko, and M.Kluge, Jour.Mat.Res. 5, 286 (1990).
- [9] A.Granato, Phys. Rev. Lett., 68, 974, (1992)
- [10] TA.Weber and FH. Stillinger, Journ. of Chem. Phys., 81, 5095, (1984)
- [11] R.W. Cahn, Nature 323, 668 (1986)
- [12] R.W. Cahn, Nature 413, 582 (2001)
- [13] A.Kanigel, J.Adler, and E.Polturak, cond.mat. 0105022, Int. Jour. of Mod. Phys. C 12, 727, (2001).
- [14] V. Sorkin, E. Polturak and Joan Adler, ArXiv:cond-mat/0304215, (2003)

- [15] J.W.M. Frenken and J.F. van der Veen, Phys. Rev. Lett. 54, 134 (1985).
- [16] J.F. van der Veen, in "Phase Transitions in Surface Films 2", H. Taub., et al., eds., Plenum Press (New York), 1991.
- [17] A. Trayanov and E. Tosatti, Phys. Rev. B, 38, 6961, (1989).
- [18] W. Lipowsky, Phys. Rev. Lett, 49, 1575, (1982).
- [19] W . Lipow sky and W . Speth, Phys. Rev. B, 28, 3938, (1983)
- [20] W. Lipowsky, U. Breuer, K. C. Prince and H. P. Bonzel, Phys. Rev. Lett., 62, 913, (1989)
- [21] O. Tom agnini, F. Ercolessi, S. Iarlori, F. D. Di Tolla and E. Tosatti, Phys. Rev. Lett., 76, 1118, (1996)
- [22] R.Ohnesorge, H.Lowen and H.Wagner, Phys. Rev. E, 50, 4801, (1994)
- [23] H. Hakkinen and M. Manninen, Phys. Rev. B, 46, 1752, (1992)
- [24] H. Hakkinen and U. Landmann, Phys. Rev. Lett., 71, 1023, (1993)
- [25] Y. Beaudet, L.J. Lew is and M. Persson, Phys. Rev. B, 50, 12084, (1994)
- [26] R.N.Bamett and U.Landman, Phys. Rev. B 44, 3226, (1991).
- [27] E.T.Chen, R.N.Bamett, and U.Landman, Phys. Rev B, 41, 439, (1990).
- [28] E.T.Chen, R.N.Bamett and U.Landman, Phys. Rev B, 40, 924, (1989).
- [29] H.Cox, R.L. Johnston and J.N. Murrel, Surf. Sci., 67, 373, (1996).
- [30] P. Stoltze, J. Chem. Phys., 92, 6306, (1990).
- [31] P. Stolze, J. K. Norskov and U. Landman, Phys. Rev. Lett., 61, 440, (1988).
- [32] J.Q. Broughton, G.H.Gilmer and K.A. Jackson, Phys. Rev. Lett., 49, 1496, (1982).
- [33] J.Q. Broughton and G.H.Gilmer, J.Chem. Phys., 79, 5119, 1983
- [34] S.R. Phillpot, S.Y ip, and D. Wolf, "Computers in Physics" 3, 20 (1989).
- [35] J. W ang, J. Li, S, Y ip, S. Phillpot and D. W olf, Phys. Rev. B 52, 12627 (1995).

- [36] J.W ang, J.Li, S, Yip, S.Phillpot and D.W olf, Physica A 240, 396 (1997).
- [37] Z.H. Jin, P. Gumbsch, K. Lu, and E. Ma, Phys. Rev. Lett., 87, 055703, (2001)
- [38] M. Finnis and J. Sinclair, Philos., Mag. A, 56, 11, (1987)
- [39] D.Rapaport, The art of M.D. simulations, Cambridge, University Press, 1991
- [40] M.P.Allen and D.J.Tildesley, Computer Simulations of Liquids, Clarendon Press, Oxford, 1987
- [41] J.Adler, A. Hashibon, N. Schreiber, A. Sorkin, S. Sorkin and G. Wagner, Comp. Phys. Comm., 12, No.5, 623, (2002) http://phycomp.technion.ac.il/aviz/index.html
- [42] J.F. Lutsko, D. Wolf, S.R. Phillipot and S.Yip, Phys. Rev. B, 40, 2841, (1989)
- [43] Handbook of Chemistry and Physics, 81'st edition 2000-2001 year, D.R. Lide, editor in chief, CRC Press
- [44] S.Foiles and M.Baskes and M.Daw, Phys. Rev. B, 33, 7983, (1986)
- [45] J. Adler, V. Sorkin and E. Polturak, submitted, http://phycomp.technion.ac.il/phr76ja/melt/